

INFORMATION DISCLOSURE STATEMENT

Applicant : Hirayama et al.

App. No : 10/590,046

Filed : June 15, 2007

For : BASE MATERIAL FOR PATTERN-
FORMING MATERIAL, POSITIVE
RESIST COMPOSITION AND
METHOD OF RESIST PATTERN
FORMATION

Examiner : Johnson, Connie P.

Art Unit : 1795

Conf. No. 5635

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(Date)

/Neil S. Bartfeld/

Neil S. Bartfeld, Ph.D., Reg. No. 39,901

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing three (three) references to be considered by the Examiner. Please place these documents in the application file.

No fees are believed to be due. However, the Commissioner is hereby authorized to charge any additional fees which may be required to Account No. 11-1410.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: April 11, 2011

By: /Neil S. Bartfeld/
Neil S. Bartfeld, Ph.D.
Registration No. 39,901
Agent of Record
Customer No. 20,995
(858) 836-9000